

ABSTRACT

A thermal processing apparatus of the present invention includes a reaction vessel in which an object to be processed is contained; a heat insulating body provided so as to surround the reaction vessel; a
5 plurality of holes provided in the heat insulating body; a plurality of annular spacer members, each of which is provided in each of the plurality of holes; and a plurality of heater elements, each of which is inserted in each of the plurality of annular spacer members.